

# Quasiparticle Band Gap Renormalization in Semiconducting Single-Layer WS<sub>2</sub> Induced by Dielectric Screening

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Pristine transition metal dichalcogenides (TMDs) exhibit a unique combination of radiation tolerance and energy-efficient carrier transport in an atomically-thin profile. However, synthesis and device fabrication processes introduce defects and interface inhomogeneity into TMDs, which perturb the electronic structure and excitation dynamics by altering the dielectric screening environment. The dielectric screening strength, and the electronic structure perturbation, are proportional to the dielectric constant ( $\epsilon$ ) of the external environment ( $\epsilon_{ext}$ ) and the TMD ( $\epsilon_{WS_2}$ ). Yet, the renormalizing effect of dielectric screening variations on the TMD electronic structure is unclear.

Here, we elucidate the impact of varying the external and internal dielectric screening strength on the electronic structure of single-layer WS<sub>2</sub>, using  $\epsilon_{ext}$  and  $\epsilon_{WS_2}$  as proxies for screening strength. We systematically vary the external screening strength through sample design including suspended WS<sub>2</sub> ( $\epsilon_{ext} \approx 2$ ) and Au-supported WS<sub>2</sub> ( $\epsilon_{ext} \approx 62$ ), and the internal screening strength by varying the WS<sub>2</sub> defect density through ion irradiation (5 MeV Fe<sup>2+</sup>, 10<sup>11</sup>-10<sup>13</sup> cm<sup>-2</sup>). We estimate the quasiparticle band gap and exciton binding energy as a function of  $\epsilon_{ext}$  and  $\epsilon_{WS_2}$  using photoemission and electron energy loss spectroscopy (PES, EELS).

PES shows the valence band density of states exhibit an increasing shift towards the vacuum level with increasing dielectric screening strength. From the offset between the charge neutrality point and valence band edge, we estimate the band gap of suspended WS<sub>2</sub> is reduced by up to 160 meV up to an ion fluence of 10<sup>13</sup> cm<sup>-2</sup>, coinciding with an increased  $\epsilon_{WS_2}$ . More substantial band gap reductions are estimated in Au-supported WS<sub>2</sub>. The estimated reduction in quasiparticle band gap primarily manifests from reduced exciton binding energy according to EELS. To enable broader application of our findings, we estimate the WS<sub>2</sub> defect density using Shockley-Read-Hall recombination. This study highlights the profound impact of the dielectric screening environment on TMD electronic structure.

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